

제22회 한국반도체학술대회

2015년 2월 10일(화) - 12일(목), 인천 송도컨벤시아

B. Patterning 분과

Room B
1F / 105호

2015년 2월 11일(수) 13:00-14:30

[WB2-B] Patterning

좌장: 유원종 (성균관대학교), 정지원 (인하대학교)

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| WB2-B-1 | 13:00-13:30 | The Fabrication of Nanocrystal based Metamaterial by Nanoimprinting
Sung-Hoon Hong ^{1,2} and In-Kyu You ¹
¹ Components & Materials Research Laboratory, Electronics and Telecommunication Research Institute (ETRI), ² Department of Advanced Device Technology, UST |
| WB2-B-2 | 13:15-13:30 | Synchronized Dual Pulse Etching Effect of SiO₂ in Capacitive Coupled C₄F₈/Ar/O₂ Plasmas
Kyung-Chae Yang, Min-Hwan Jeon, Hyun-Woo Sung, and Geun-Young Yeom
Department of Advanced material science and Engineering, SungKyunkwan University |
| WB2-B-3 | 13:30-13:45 | 그래핀 접촉저항 감소를 위한 플라즈마기술
라창호, 최민섭, 유원종
SSKU Advanced Institute of Nano Technology, Sungkyunkwan University |
| WB2-B-4 | 13:45-14:00 | Inductively Coupled Plasma Type Etcher의 ESC Edge Ring 소재 적합성 분석
김형준, 김무진, 원복연, 장기수, 구덕자, 민경진, 최길현
삼성전자 반도체연구소 |
| WB2-B-5 | 14:00-14:15 | RF Plasma SiNx Etching Fault Detection using Optical Emission Spectra with Modified K-Means Cluster Analysis and Principal Component Analysis
Haegy Jang ¹ , Hakseung Lee ² , and Heeyeop Chae ^{1,2}
¹ SSKU Advanced Institute of Nanotechnology, Sungkyunkwan University, ² School of Chemical Engineering, Sungkyunkwan University |
| WB2-B-6 | 14:15-14:30 | Plasma-Assisted Preparation of Metal Nanoparticles on the Branched Nanowires to Enhance the Gas Sensing Properties
Han Gil Na ¹ , Yong Jung Kwon ¹ , Hong Yeon Cho ¹ , Chongmu Lee ² , and Hyoun Woo Kim ¹
¹ Division of Materials Science and Engineering, Hanyang University, ² Department of Materials Science and Engineering, Inha University |